

On the influence of electrode surfaces on the plasma chemistry and striations in a capacitive chlorine discharge

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The *oopd1 1d-3v PIC/MCC code*

- We consider a chlorine discharge that consists of:
 - electrons
 - the ground state chlorine molecule $\text{Cl}_2(X^1\Sigma_g^+, v = 0)$,
 - the ground state chlorine atom $\text{Cl}(3p^5\ ^2P)$
 - the negative chlorine ion Cl^-
 - the positive chlorine ions Cl^+ and Cl_2^+

Huang and Gudmundsson (2013) *Plasma Sources Sci. Technol.*, **22**(5) 055020

- We use the *oopd1* (objective oriented plasma device for one dimension) code to simulate the discharge
- The *oopd1* code was originally developed at the Plasma Theory and Simulation Group at UC Berkeley
- It has 1 dimension in space and 3 velocity components for particles (1d-3v)

Gudmundsson et al. (2013) *Plasma Sources Sci. Technol.*, **22**(3) 035011

Wen et al. (2021) *Plasma Sources Sci. Technol.*, **30**(10) 105009



Electron power absorption

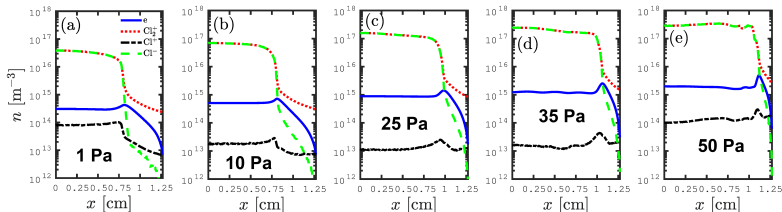
Voltage source operated at a single frequency

$$V(t) = V_{\text{rf}} \sin(2\pi ft)$$

gap = 2.54 cm, $V_{\text{rf}} = 222$ V and $f = 13.56$ MHz



Electron power absorption



Proto and Gudmundsson (2021) PSST 30(6) 065009

- The time averaged charged particle density profiles of a parallel plate capacitively coupled chlorine discharge
- At low pressures, the profile for Cl₂⁺ ions is cosine-like or parabolic since Cl₂⁺ ions are lost mainly due to diffusion to the walls
- As the pressure increases, the recombination between Cl₂⁺ and Cl⁻ ions becomes the major loss mechanism for Cl₂⁺ ions and the density profile for Cl₂⁺ and Cl⁻ ions becomes flat in the bulk region



Electron power absorption

- To determine the electron power absorption mechanisms we apply Boltzman term analysis

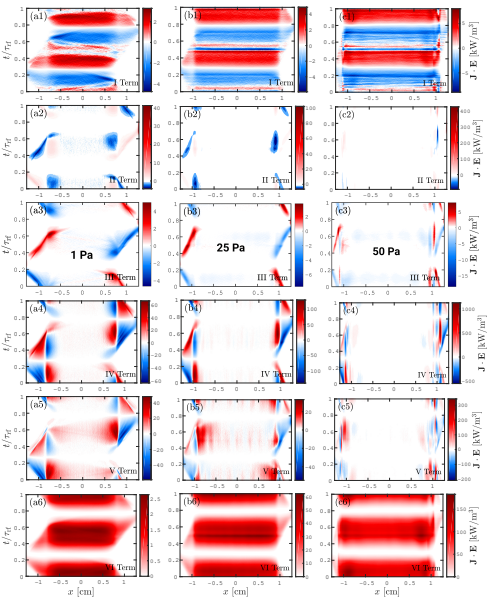
$$\begin{aligned} J_e \cdot E = & \underbrace{m_e u_e n_e \frac{\partial u_e}{\partial t}}_I - \underbrace{m_e u_e^3 \frac{\partial n_e}{\partial x}}_II - \underbrace{m_e u_e^2 \frac{\partial n_e}{\partial t}}_III \\ & + \underbrace{e u_e T_e \frac{\partial n_e}{\partial x}}_IV + \underbrace{e n_e u_e \frac{\partial T_e}{\partial x}}_V + \underbrace{m_e n_e \nu_c u_e^2}_VI \end{aligned} \quad (1)$$

Surendra and Dalvie (1993) PRE **48**(5) 3914 and Schulze et al. (2018) **27**(5) 055010

- Terms I and III – power absorption due to electron inertia
- Term II – the electron density gradient
- Term IV – ambipolar field – electron density gradient
- Term V – the electron temperature gradient
 - Terms IV and V represent pressure or collisionless heating
- Term VI – electron neutral collisions or Ohmic heating



Electron power absorption

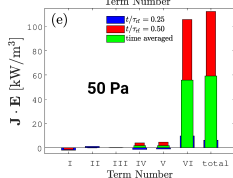
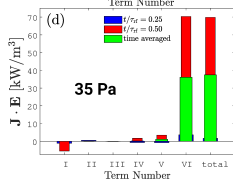
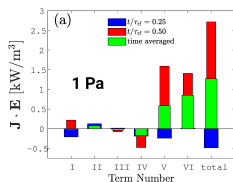


- The spatio temporal behavior of the various terms that constitute the electron power absorption
 - Terms I and III – electron inertia
 - Term II – electron density gradient
 - Terms IV and V – pressure (collisionless) heating
 - Term VI – Ohmic heating

Electron power absorption

- The space averaged electron power absorption profile terms
 - $t/\tau_{rf} = 0.25$ blue bar
 - $t/\tau_{rf} = 0.5$ red bar
 - time averaged green bar
- At 1 Pa the pressure terms and the Ohmic term contribute to the electron power absorption
- At higher pressures Ohmic power absorption dominates

Proto and Gudmundsson (2021) PSST **30**(6) 065009



Surface effects

Voltage source operated at a single frequency

$$V(t) = V_{\text{rf}} \sin(2\pi ft)$$

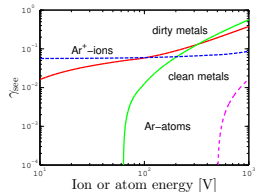
gap = 2.54 cm, $V_{\text{rf}} = 222$ V and $f = 13.56$ MHz



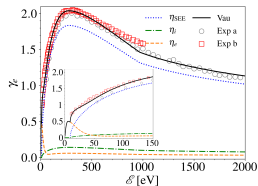
Secondary electron emission

Secondary electron emission due to

- ion bombardment of the electrodes
- neutral bombardment of the electrodes
 - Using fits for argon bombardment developed by Phelps and Petrović (1999)
- electron bombardment of the electrodes
 - Using the modified Vaughan method as described by Wen et al. (2023)



based on Phelps and Petrović (1999) PSST 8 R21



Secondary electron emission – the cases explored

Case	cross section	neutrals	ions	electrons
I	old	0.0	0.0	0.0
II	new	0.0	0.0	0.0
III	new	$\gamma_{\text{see},n}(\mathcal{E}_n)$	$\gamma_{\text{see},i}(\mathcal{E}_i)$	0.0
IV	new	$\gamma_{\text{see},n}(\mathcal{E}_n)$	$\gamma_{\text{see},i}(\mathcal{E}_i)$	$\gamma_{\text{see},e}(\mathcal{E}_e, \theta)$
V	new	0.0	0.5	0.0

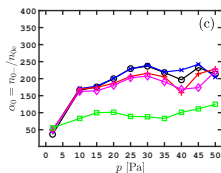
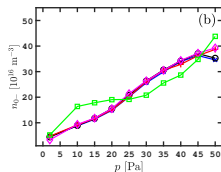
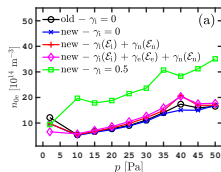
- In Cases I and II the secondary electron emission processes are neglected
- Case III assumes only neutral and ion induced energy dependent secondary electron emission yield
- Case IV has in addition electron induced secondary electron emission
- Case V assumes only a constant ion induced secondary electron emission yield



Secondary electron emission

- The electron density, the Cl^- density, and the electronegativity in the discharge center (α_0) versus pressure
- With increasing pressure the electronegativity in the discharge center α_0 increases before it stabilizes at a relatively constant level
- Secondary electron emission from the electrodes leads to a reduction in electronegativity, which is especially noticeable at higher pressures

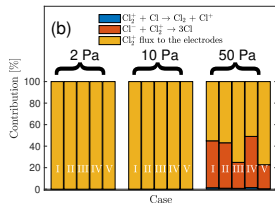
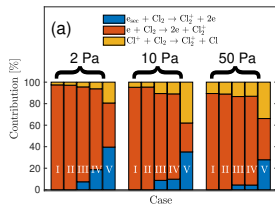
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Secondary electron emission

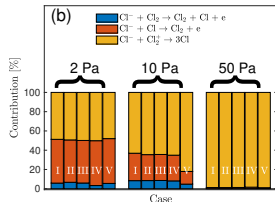
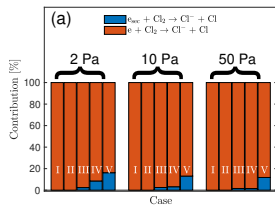
- The creation and loss of Cl_2^+ ions
- Electron impact ionization creates the Cl_2^+ ions
- At the lower pressures the Cl_2^+ ions are almost entirely lost as they bombard the electrodes
- With increasing pressure to 50 Pa the role of ion-ion mutual recombination increases

Mahdavi pour and Gudmundsson (2024) PSST **33**(6) 065006



Secondary electron emission

- The creation and loss of Cl^- ions
- The creation of the negative ion Cl^- is almost entirely due to dissociative attachment
- The dominating loss processes for the negative ion Cl^- at 50 Pa is ion-ion mutual neutralization $\text{Cl}^- + \text{Cl}_2^+$
- Lowering the pressure associative detachment by the Cl atom and detachment by the Cl_2 molecule play an increasing role, with over 50 % contribution at 2 Pa



Striations

Voltage source operated at a single frequency

$$V(t) = V_{\text{rf}} \sin(2\pi ft)$$

gap = 2.54 cm, $V_{\text{rf}} = 222$ V and $f = 13.56$ MHz

$$\gamma_i(\mathcal{E}_i) + \gamma_n(\mathcal{E}_n) + \gamma_e(\mathcal{E}_e, \theta)$$

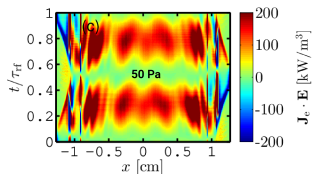
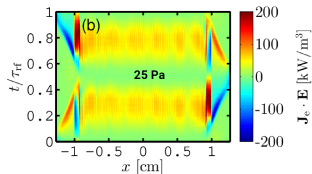
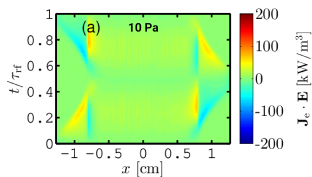


Secondary electron emission

- The spatio-temporal behaviour of primary electron power absorption for the most realistic secondary electron emission model

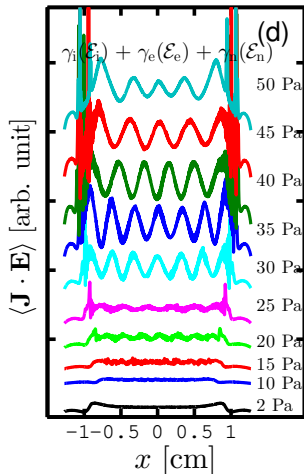
$$\gamma_{\text{total}} = \gamma_i(\mathcal{E}_i) + \gamma_n(\mathcal{E}_n) + \gamma_e(\mathcal{E}_e, \theta)$$

- There is a clear indication of the α -mode and the drift-ambipolar (DA) mode
- At higher pressure of 25 and 50 Pa we observe an increase in electron power absorption and pronounced striation structure



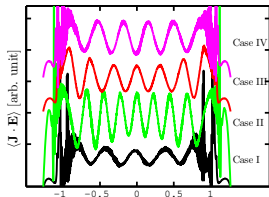
Secondary electron emission

- Primary electron power absorption as the pressure is varied
- We observe striation pattern at 15 Pa
- Above 15 Pa the striation amplitude increases with increased pressure up to 35 Pa, and then decreases
- The number of striations decreases with increased pressure



Secondary electron emission

- The primary electron power absorption profiles while varying the secondary emission processes (Cases I – IV) at 40 Pa
- Case II ($\gamma_i = 0.5$) exhibits the highest number of striations, while Case I (no secondary emission) has the lowest number
- It appears that including secondary electron emission in the discharge model increases both the amplitude and the number of the striations
- This contradicts what has been observed for a capacitive oxygen (Wang et al., 2019) and CF_4 (Wang et al., 2023) discharges

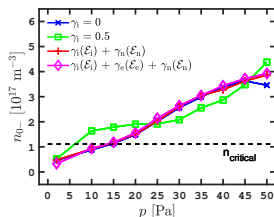


Secondary electron emission

- Striations are known to appear in electronegative discharges when two conditions are simultaneously fulfilled:
 - high enough electronegativity
 - driving frequency that is comparable to the ion plasma frequency
- Based on the ion-ion plasma model striations may appear when $n_{\text{ion}} > n_{\text{critical}}$ where the critical density is defined as (Liu et al., 2017)

$$n_{\text{critical}} = \frac{\omega_{\text{rf}}^2 \epsilon_0 \mu}{e^2}$$

where $\mu = m_+ m_- / (m_+ + m_-)$ is the reduced mass of the positive and negative ions



Summary



Summary

- The chlorine discharge exhibits high electronegativity
- At the lowest pressure (1 Pa) the electron power absorption is due to both the pressure and the Ohmic terms and at higher pressure Ohmic terms dominate (drift-ambipolar (DA) mode)
- Striations start to appear in the discharge bulk at pressure around 15 Pa and peak in amplitude for pressure around 40 Pa and then decline again
- We find that the amplitude and the number of striations increase with the addition of secondary electron emission to the discharge model



Thank you for your attention

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